

Roll No.:

National Institute of Technology, Delhi

Name of the Examination: B. Tech (Make Up)

Branch : ECE

Semester : III

Title of the Course : Solid State Devices

Course Code : ECB 201

Time: 3 Hours

Maximum Marks: 50

Note:

- Questions are printed on BOTH sides. Answers should be CLEAR AND TO THE POINT.
- All parts of a single question must be answered together. ELSE QUESTION SHALL NOT BE EVALUATED.

Use following data if not given in a problem: $\epsilon_0 = 8.85 \times 10^{-14} \text{ F/cm}$, $\epsilon_r (\text{SiO}_2) = 3.9$, $\epsilon_r (\text{Si}) = 11.8$, At room temperature for Si $[\mu_n = 1350 \text{ cm}^2/\text{V}\cdot\text{S}$, $\mu_p = 480 \text{ cm}^2/\text{V}\cdot\text{S}$, $n_i = 1.5 \times 10^{10} / \text{cm}^3$, $E_g = 1.12 \text{ eV}$, $k = 8.62 \times 10^{-5} \text{ eV/K}$, $\tau_n = \tau_p = 1 \mu\text{s}$, $E_g(\text{Ge}) = 0.7 \text{ eV}$, $n_i(\text{Ge}) = 2.5 \times 10^{13} / \text{cm}^3$.

1. Comment on the following with brief and to the point logical explanation: [1+1+1+2]
 - (a) Variation of band gap with doping.
 - (b) Variation of band gap with temperature.
 - (c) Variation of lattice controlled mobility with temp.
 - (d) Variation of intrinsic carrier concentrations (n_i) with temp and band gap (E_g).
2. Write brief note on followings: [2 * 5 = 10]
 - (a) Thermal Runway
 - (b) Base narrowing effect and early effect
 - (c) Enhancement mode MOSFET
 - (d) p-i-n diode
 - (e) Hall effect
3. A metal-semiconductor (MS) junction is made between a metal of work function $\phi_m = 4.6 \text{ eV}$ and a p-type Si doped with $1.5 \times 10^{14} / \text{cm}^3$ at room temp. Sketch and label the energy band diagrams across the MS junction before contact and after contact. [$\chi_{\text{Si}} = 4.05 \text{ eV}$]. [2.5 + 2.5]
4. Consider a Ge crystal at room temperature doped with $5 \times 10^{17} / \text{cm}^3$ As atoms. Find [5]
equilibrium electron, hole concentrations and position of the Fermi level w.r.t intrinsic energy level (E_i) and conduction energy band (E_c). Draw the energy band diagram also.
5. For a Si bar having length $4 \mu\text{m}$, doped n-type at $10^{17} / \text{cm}^3$. Calculate the current for an [5]
applied voltage of 2 V having a cross sectional area of 0.01 cm^2 . If the voltage is now raised at 100 V what will be the change in current? Electron and hole mobility are $1350 \text{ cm}^2/\text{V}\cdot\text{sec}$ and $400 \text{ cm}^2/\text{V}\cdot\text{sec}$ for low electric field. For higher field, saturation velocity for electron is $V_s = 10^7 \text{ cm/sec}$.
6. Consider a Si sample kept at room temperature having band gap $E_g = 1.12 \text{ eV}$. [5]

- (a) If the Fermi level E_F , is located exactly at the middle of the band gap for this sample, then what will be the probability of finding an electron at $E = E_C + 2KT$.
- (b) If the Fermi level E_F , is located such that $E_F = E_V$, then what will be the probability of finding an electron at $E = E_V + KT$.

Note: Put "Tick (✓)" Marks on the write option wherever applicable (Bold) / Fill in the blanks.

7. (a) In an $n\text{pn}$ $\text{Si}/\text{Si}_{1-x}\text{Ge}_x$ heterojunction bipolar transistor (HBT), base is **heavily/ lightly** [2]
doped and increases the **hole/ electron** injection efficiency.
- (b) Body or substrate bias effect **increases/ decreases** the current in MOSFETs and [2]
Boron ion implantation **increases/ decreases** the threshold voltage (V_T) in n-channel
MOSFETs.
- (c) Usually in MOS scaling, the oxide layer thickness **increases/ decreases** and gate [2]
capacitance of the device **increases/ decreases**.
- (d) Substrate leakage current in n-MOS devices are due to secondary **electrons/ holes** [2]
and this current **increases/ reduces** at higher gate voltage.
- (e) Avalanche breakdown voltage **increases/ decreases** as band gap of the [2]
semiconductor increases and this voltage **increases/ decreases** as doping of the
lighter region decreases.
- (f) The probability of finding an electron at an energy level $4kT$ above the Fermi level [2]
would be 0.0183 and number of electrons would be $0.0183 \times 10^{19} / \text{cm}^3$ if the
density of states is $10^{19} / \text{cm}^3$.
- (g) For a Si at a given temperature it is found that 1×10^{10} electrons/ cm^3 have moved from [3]
valance band (VB) to conduction band (CB) when density of atoms is $10^{22} / \text{cm}^3$. Then
number of holes in the VB would be 10^{10} and this will be a factor of value
 10^{-11} of the total available electrons in the VB.

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